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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuya OTA, Akikazu TANIMOTO, Tsuneyuki HAGIWARA,
Hideki KOMATSUDA and Takashi MORI

New Rule 1.53(b) Continuation of Application No. 09/396,349

Filed: May 2, 2001

Docket No.: 104313.01

For: APPARATUS AND METHOD FOR PATTERN EXPOSURE
AND METHOD FOR ADJUSTING THE APPARATUS

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 3,4 and 15-17 as follows:

3. (Amended) A method according to claim 1, wherein said exposure apparatus is provided with projection optics consisted of reflective components for focusing illumination light exiting from a mask so as to project a pattern fabricated on said mask on a substrate base, wherein adjustments of optical components in at least a part of said illumination optics and said projection optics are performed using said non-exposure light emitted from said wide bandwidth light source.

4. (Amended) A method according to claim 1, wherein said wide bandwidth light source generates light having wavelengths in an extreme ultraviolet range as said

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